Mark J Kushner

List of Publications by Year
in descending order

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233 papers	10,994 citations	28242 55 h-index	39638 94 g-index
236 all docs	236 docs citations	236 times ranked	4990 citing authors

#	Article	IF	Citations
1	Particle trapping, size-filtering, and focusing in the nonthermal plasma synthesis of sub-10 nanometer particles. Journal Physics D: Applied Physics, 2022, 55, 235202.	1.3	7
2	Atmospheric pressure plasma functionalization of polystyrene. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2022, 40, .	0.9	5
3	Propagation of positive discharges in an air bubble having an embedded water droplet. Plasma Sources Science and Technology, 2021, 30, 015005.	1.3	15
4	Propagation of atmospheric pressure plasmas through interconnected pores in dielectric materials. Journal of Applied Physics, 2021, 129, .	1.1	10
5	Plasma-driven solution electrolysis. Journal of Applied Physics, 2021, 129, .	1.1	58
6	Scaling of atomic layer etching of SiO2 in fluorocarbon plasmas: Transient etching and surface roughness. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2021, 39, 033003.	0.9	6
7	Electric field reversals resulting from voltage waveform tailoring in Ar/O₂ capacitively coupled plasmas sustained in asymmetric systems. Plasma Sources Science and Technology, 2021, 30, 085002.	1.3	10
8	Plasma-enhanced atomic layer deposition of SiO2 film using capacitively coupled Ar/O2 plasmas: A computational investigation. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2021, 39, 052403.	0.9	4
9	Erosion of focus rings in capacitively coupled plasma etching reactors. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2021, 39, .	0.9	9
10	Guided plasma jets directed onto wet surfaces: angular dependence and control. Journal Physics D: Applied Physics, 2021, 54, 045206.	1.3	13
11	Interactions between atmospheric pressure plasmas and metallic catalyst particles in packed bed reactors. Journal Physics D: Applied Physics, 2021, 54, 104001.	1.3	23
12	10.1063/5.0069141.1. , 2021, , .		0
13	Positive charging of grains in an afterglow plasma is enhanced by ions drifting in an electric field. Physics of Plasmas, 2021, 28, .	0.7	23
14	Scaling of silicon nanoparticle growth in low temperature flowing plasmas. Journal of Applied Physics, 2021, 130, .	1.1	6
15	Formation of surface ionization waves in a plasma enhanced packed bed reactor for catalysis applications. Chemical Engineering Journal, 2020, 382, 123038.	6.6	25
16	Helium plasma jet interactions with water in well plates. Plasma Processes and Polymers, 2020, 17, 1900179.	1.6	13
17	Generation of reactive species in water film dielectric barrier discharges sustained in argon, helium, air, oxygen and nitrogen. Journal Physics D: Applied Physics, 2020, 53, 435206.	1.3	27
18	Ionization wave propagation in a He plasma jet in a controlled gas environment. Journal of Applied Physics, 2020, 128, 083301.	1.1	18

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19	Transients using low-high pulsed power in inductively coupled plasmas. Plasma Sources Science and Technology, 2020, 29, 085006.	1.3	8
20	Highly selective Si3N4/SiO2etching using an NF3/N2/O2/H2remote plasma. I. Plasma source and critical fluxes. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2020, 38, 023007.	0.9	22
21	Pattern dependent profile distortion during plasma etching of high aspect ratio features in SiO2. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2020, 38, .	0.9	30
22	Power matching to pulsed inductively coupled plasmas. Journal of Applied Physics, 2020, 127, .	1.1	22
23	Scaling of pulsed nanosecond capillary plasmas at different specific energy deposition. Plasma Sources Science and Technology, 2020, 29, 125006.	1.3	5
24	Highly selective Si3N4/SiO2 etching using an NF3/N2/O2/H2 remote plasma. II. Surface reaction mechanism. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2020, 38, .	0.9	17
25	Microneedle Penetrating Array with Axon-Sized Dimensions for Cuff-less Peripheral Nerve Interfacing. , 2019, , .		4
26	Ionization wave propagation in an atmospheric pressure plasma multi-jet. Plasma Sources Science and Technology, 2019, 28, 125009.	1.3	26
27	Three-dimensional measurements of plasma parameters in an inductively coupled plasma processing chamber. Physics of Plasmas, 2019, 26, .	0.7	21
28	Filamentation of capacitively coupled plasmas in large magnetic fields. Physics of Plasmas, 2019, 26, .	0.7	14
29	Atmospheric pressure plasma activation of water droplets. Journal Physics D: Applied Physics, 2019, 52, 355207.	1.3	66
30	Plasma etching of high aspect ratio features in SiO2 using Ar/C4F8/O2 mixtures: A computational investigation. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2019, 37, .	0.9	64
31	Plasma kinetics in a nanosecond pulsed filamentary discharge sustained in Arâ€"H2O and H2O. Journal Physics D: Applied Physics, 2019, 52, 044003.	1.3	38
32	Atmospheric pressure plasma jets onto a reactive water layer over tissue: pulse repetition rate as a control mechanism. Journal Physics D: Applied Physics, 2019, 52, 015201.	1.3	29
33	Downstream etching of silicon nitride using continuous-wave and pulsed remote plasma sources sustained in Ar/NF3/O2 mixtures. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2018, 36, .	0.9	17
34	Interaction of positive streamers in air with bubbles floating on liquid surfaces: conductive and dielectric bubbles. Plasma Sources Science and Technology, 2018, 27, 015016.	1.3	12
35	Consequences of atomic layer etching on wafer scale uniformity in inductively coupled plasmas. Journal Physics D: Applied Physics, 2018, 51, 155201.	1.3	18
36	Numerical study of the influence of surface reaction probabilities on reactive species in an rf atmospheric pressure plasma containing humidity. Plasma Physics and Controlled Fusion, 2018, 60, 014035.	0.9	22

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37	Molecular admixtures and impurities in atmospheric pressure plasma jets. Journal of Applied Physics, 2018, 124, .	1.1	45
38	Transient behavior in quasi-atomic layer etching of silicon dioxide and silicon nitride in fluorocarbon plasmas. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2018, 36, .	0.9	45
39	Electrode configurations in atmospheric pressure plasma jets: production of reactive species. Plasma Sources Science and Technology, 2018, 27, 105020.	1.3	39
40	Chemical kinetics in an atmospheric pressure helium plasma containing humidity. Physical Chemistry Chemical Physics, 2018, 20, 24263-24286.	1.3	62
41	Time-resolved evolution of micro-discharges, surface ionization waves and plasma propagation in a two-dimensional packed bed reactor. Plasma Sources Science and Technology, 2018, 27, 085002.	1.3	32
42	A general memristor-based partial differential equation solver. Nature Electronics, 2018, 1, 411-420.	13.1	183
43	Spatio-temporal plasma heating mechanisms in a radio frequency electrothermal microthruster. Plasma Sources Science and Technology, 2018, 27, 085011.	1.3	10
44	Controlling VUV photon fluxes in pulsed inductively coupled Ar/Cl₂plasmas and potential applications in plasma etching. Plasma Sources Science and Technology, 2017, 26, 024005.	1.3	32
45	Role of neutral transport in aspect ratio dependent plasma etching of three-dimensional features. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2017, 35, .	0.9	44
46	Propagation of negative electrical discharges through 2-dimensional packed bed reactors. Journal Physics D: Applied Physics, 2017, 50, 025203.	1.3	65
47	Atomic layer etching of 3D structures in silicon: Self-limiting and nonideal reactions. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2017, 35, .	0.9	47
48	Calculated cross sections for electron collisions with NF₃, NF₂and NF with applications to remote plasma sources. Plasma Sources Science and Technology, 2017, 26, 065010.	1.3	45
49	Insights to scaling remote plasma sources sustained in NF3mixtures. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2017, 35, 031302.	0.9	23
50	The role of thermal energy accommodation and atomic recombination probabilities in low pressure oxygen plasmas. Plasma Physics and Controlled Fusion, 2017, 59, 024004.	0.9	19
51	Investigation of feature orientation and consequences of ion tilting during plasma etching with a three-dimensional feature profile simulator. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2017, 35, .	0.9	34
52	Enhanced control of the ionization rate in radio-frequency plasmas with structured electrodes via tailored voltage waveforms. Plasma Sources Science and Technology, 2017, 26, 125005.	1.3	16
53	Properties of arrays of microplasmas: application to control of electromagnetic waves. Plasma Sources Science and Technology, 2017, 26, 105006.	1.3	12
54	Effects of a chirped bias voltage on ion energy distributions in inductively coupled plasma reactors. Journal of Applied Physics, 2017, 122, .	1.1	4

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55	Plasma-induced flow instabilities in atmospheric pressure plasma jets. Applied Physics Letters, 2017, 111, .	1.5	49
56	Contact Edge Roughness In The Etching Of High Aspect Ratio Contacts In Sio<inf>2</inf>. , 2017, , .		0
57	Synthesis of Silicon Nanoparticles in Nonthermal Capacitively-Coupled Flowing Plasmas: Processes and Transport. Plasma Chemistry and Plasma Processing, 2016, 36, 941-972.	1.1	25
58	Helium atmospheric pressure plasma jets interacting with wet cells: delivery of electric fields. Journal Physics D: Applied Physics, 2016, 49, 185201.	1.3	56
59	The consequences of air flow on the distribution of aqueous species during dielectric barrier discharge treatment of thin water layers. Plasma Sources Science and Technology, 2016, 25, 055020.	1.3	21
60	Air plasma treatment of liquid covered tissue: long timescale chemistry. Journal Physics D: Applied Physics, 2016, 49, 425204.	1.3	149
61	Origins of aspect ratio dependent etching in plasma materials processing. , 2016, , .		0
62	Plasma formation during operation of diode (DPAL) and excimer (XPAL) pumped alkali lasers. , 2016, , .		0
63	Optimizing remote plasma sources for selective etching. , 2016, , .		0
64	Electron collisions with atoms, ions, molecules, and surfaces: Fundamental science empowering advances in technology. Proceedings of the National Academy of Sciences of the United States of America, 2016, 113, 7026-7034.	3.3	99
65	Helium atmospheric pressure plasma jets touching dielectric and metal surfaces. Journal of Applied Physics, 2015, 118, 013301.	1.1	167
66	Propagation mechanisms of guided streamers in plasma jets: the influence of electronegativity of the surrounding gas. Plasma Sources Science and Technology, 2015, 24, 035022.	1.3	89
67	Controlling VUV photon fluxes in low-pressure inductively coupled plasmas. Plasma Sources Science and Technology, 2015, 24, 034017.	1.3	38
68	Formation of reactive oxygen and nitrogen species by repetitive negatively pulsed helium atmospheric pressure plasma jets propagating into humid air. Plasma Sources Science and Technology, 2015, 24, 035026.	1.3	150
69	Long-term effects of multiply pulsed dielectric barrier discharges in air on thin water layers over tissue: stationary and random streamers. Journal Physics D: Applied Physics, 2015, 48, 494002.	1.3	39
70	Experimental and numerical study of fast gas heating and O atom production in a capillary nanosecond discharge. , 2014, , .		5
71	Electron energy distributions in a magnetized inductively coupled plasma. Physics of Plasmas, 2014, 21, 093512.	0.7	16
72	Control of ion energy distributions using phase shifting in multi-frequency capacitively coupled plasmas. , 2014, , .		0

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73	Atmospheric pressure plasma jets interacting with liquid covered tissue: touching and not-touching the liquid. Journal Physics D: Applied Physics, 2014, 47, 475203.	1.3	164
74	Branching and path-deviation of positive streamers resulting from statistical photon transport. Plasma Sources Science and Technology, 2014, 23, 065041.	1.3	33
75	Investigation of capillary nanosecond discharges in air at moderate pressure: comparison of experiments and 2D numerical modelling. Journal Physics D: Applied Physics, 2014, 47, 365202.	1.3	33
76	Atmospheric pressure dielectric barrier discharges interacting with liquid covered tissue. Journal Physics D: Applied Physics, 2014, 47, 165201.	1.3	201
77	Electron current extraction from radio frequency excited micro-dielectric barrier discharges. Journal of Applied Physics, 2013, 113, 033301.	1.1	11
78	Atmospheric pressure plasmas penetrating through a packed-bed reactor. , 2013, , .		0
79	Arrays of atmospheric pressure microplasma jets: He/O<inf>2</inf> and Ar jets into air. , 2013, , .		0
80	The interaction of atmospheric pressure plasmas with liquid covered tissues. , 2013, , .		0
81	2-dimensional ion velocity distributions measured by laser-induced fluorescence above a radio-frequency biased silicon wafer. Physics of Plasmas, 2013, 20, 083506.	0.7	6
82	Space and phase resolved ion energy and angular distributions in single- and dual-frequency capacitively coupled plasmas. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2013, 31, .	0.9	19
83	Glow-like atmospheric pressure micro-discharges produced by charge rollers. , 2013, , .		0
84	Computational investigation of dual-frequency power transfer in capacitively coupled plasmas. , 2013, , .		0
85	Control of electron energy distributions in inductively coupled plasmas using tandem sources. , 2013, , .		0
86	Numerical simulation of a microwave driven low pressure plasma for pet bottle treatment. , 2012, , .		0
87	Numerical simulation of a coaxial microplasma jet at atmospheric pressure. , 2012, , .		0
88	Ion activation energy delivered to wounds by atmospheric pressure dielectric-barrier discharges: sputtering of lipid-like surfaces. Journal Physics D: Applied Physics, 2012, 45, 115203.	1.3	64
89	Control of electron energy distributions and plasma characteristics of dual frequency, pulsed capacitively coupled plasmas sustained in Ar and Ar/CF₄/O₂. Plasma Sources Science and Technology, 2012, 21, 055028.	1.3	42
90	The 2012 Plasma Roadmap. Journal Physics D: Applied Physics, 2012, 45, 253001.	1.3	511

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91	Independently controlled rf micro-dielectric barrier discharge arrays. , 2011, , .		0
92	Observations of electric discharge streamer propagation and capillary oscillations on the surface of air bubbles in water. Journal Physics D: Applied Physics, 2011, 44, 082001.	1.3	75
93	Experimental and modeling analysis of fast ionization wave discharge propagation in a rectangular geometry. Physics of Plasmas, 2011, 18, .	0.7	73
94	Glow-to-arc transition in mercury-free HID lamps: Cathode phenomena and salt evaporation model. , 2011, , .		0
95	Ionization wave propagation on a micro cavity plasma array. Applied Physics Letters, 2011, 99, .	1.5	19
96	Modeling of implantation and mixing damage during etching of SiO2 over Si in fluorocarbon plasmas. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2011, 29, .	0.9	20
97	Direct and indirect treatment of living tissue: Dielectric barrier discharges VS. plasma jets. , 2011, , .		0
98	Dynamics of Dielectric Barrier Discharges Over Wounded Skin. IEEE Transactions on Plasma Science, 2011, 39, 2964-2965.	0.6	8
99	Time-Resolved Electron Energy Distributions and Plasma Characteristics in a Pulsed Capacitively Coupled Plasma. IEEE Transactions on Plasma Science, 2011, 39, 2542-2543.	0.6	1
100	Fundamentals of gas phase plasmas for treatment of human tissue. Studies in Health Technology and Informatics, 2011, 163, 297-303.	0.2	2
101	Fluorine Plasma Treatments of Polypropylene Films, 1 â€“ Surface Characterization. Plasma Processes and Polymers, 2010, 7, 107-122.	1.6	32
102	Fluorine Plasma Treatments of Poly(propylene) Films, 2 â€“ Modeling Reaction Mechanisms and Scaling. Plasma Processes and Polymers, 2010, 7, 123-150.	1.6	26
103	Modeling of mercury-free HID lamps: Kinetics and thermodynamcs. , 2010, , .		0
104	The interaction of plasma filaments in DBDS with wounded skin. , 2010, , .		0
105	450 mm dual frequency capacitively coupled plasma sources: Conventional, graded, and segmented electrodes. Journal of Applied Physics, 2010, 108, 113306.	1.1	50
106	High energy electron fluxes in dc-augmented capacitively coupled plasmas. II. Effects on twisting in high aspect ratio etching of dielectrics. Journal of Applied Physics, 2010, 107, .	1.1	67
107	Sealing of porous low-k dielectrics during plasma etching with H<inf>2</inf> plasma cleaning. , 2010, , .		0
108	Modeling of micro-dielectric barrier discharges. , 2010, , .		0

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109	A computational study of interactions of multiple plasma filaments in DBDs with human skin. , 2010, , .		0
110	High energy electron fluxes in dc-augmented capacitively coupled plasmas I. Fundamental characteristics. Journal of Applied Physics, 2010, 107, 023308.	1.1	26
111	Plasma atomic layer etching using conventional plasma equipment. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2009, 27, 37-50.	0.9	145
112	Sumulation of porous low-k dielectric sealing by combined He and NH<inf>3</inf> plasma treatment. , 2009, , .		0
113	Hybrid modelling of low temperature plasmas for fundamental investigations and equipment design. Journal Physics D: Applied Physics, 2009, 42, 194013.	1.3	291
114	Structure of positive streamers inside gaseous bubbles immersed in liquids. Journal Physics D: Applied Physics, 2009, 42, 132003.	1.3	98
115	Microdischarges for use as microthrusters: modelling and scaling. Journal Physics D: Applied Physics, 2008, 41, 105208.	1.3	22
116	Ion energy and angular distributions into the waferâ€"focus ring gap in capacitively coupled discharges. Journal Physics D: Applied Physics, 2008, 41, 062004.	1.3	29
117	Seasoning of plasma etching reactors: Ion energy distributions to walls and real-time and run-to-run control strategies. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2008, 26, 498-512.	0.9	40
118	Continuous processing of polymers in repetitively pulsed atmospheric pressure discharges with moving surfaces and gas flow. Journal Physics D: Applied Physics, 2007, 40, 6953-6968.	1.3	43
119	Penetration of plasma into the wafer-focus ring gap in capacitively coupled plasmas. Journal of Applied Physics, 2007, 101, 113307.	1.1	31
120	Characteristics of pulsed plasma doping sources for ultrashallow junction formation. Journal of Applied Physics, 2007, 101, 063305.	1.1	7
121	Multi-scale simulation of functionalization of rough polymer surfaces using atmospheric pressure plasmas. Journal Physics D: Applied Physics, 2006, 39, 1594-1598.	1.3	25
122	Streamer dynamics in gases containing dust particles. Plasma Sources Science and Technology, 2006, 15, 591-602.	1.3	62
123	Integrated feature scale modeling of plasma processing of porous and solid SiO2. II. Residual fluorocarbon polymer stripping and barrier layer deposition. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2004, 22, 1260-1274.	0.9	19
124	Properties of c-C[sub 4]F[sub 8] inductively coupled plasmas. II. Plasma chemistry and reaction mechanism for modeling of Ar/c-C[sub 4]F[sub 8]/O[sub 2] discharges. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2004, 22, 511.	0.9	116
125	Pulsed plasmas as a method to improve uniformity during materials processing. Journal of Applied Physics, 2004, 96, 82-93.	1.1	56
126	Modeling of magnetically enhanced capacitively coupled plasma sources: Ar/C4F8/O2 discharges. Journal of Applied Physics, 2004, 95, 834-845.	1.1	37

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127	A Monte Carlo simulation of radiation trapping in electrodeless gas discharge lamps. Journal Physics D: Applied Physics, 2004, 37, 1780-1791.	1.3	26
128	Integrated feature scale modeling of plasma processing of porous and solid SiO2. I. Fluorocarbon etching. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2004, 22, 1242-1259.	0.9	53
129	Modeling of microdischarge devices: Pyramidal structures. Journal of Applied Physics, 2004, 95, 846-859.	1.1	143
130	O2(Î"1) production in Heâˆ•O2 mixtures in flowing low pressure plasmas. Journal of Applied Physics, 2004, 96, 2451-2465.	1.1	250
131	A Comparison of Corona-Treated and Flame-Treated Polypropylene Films. Plasmas and Polymers, 2003, 8, 61-95.	1.5	161
132	A model for plasma modification of polypropylene using atmospheric pressure discharges. Journal Physics D: Applied Physics, 2003, 36, 666-685.	1.3	415
133	Influence of modeling and simulation on the maturation of plasma technology: Feature evolution and reactor design. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2003, 21, S152-S156.	0.9	33
134	Modeling of magnetically enhanced capacitively coupled plasma sources: Ar discharges. Journal of Applied Physics, 2003, 94, 1436-1447.	1.1	78
135	Angular anisotropy of electron energy distributions in inductively coupled plasmas. Journal of Applied Physics, 2003, 94, 5522-5529.	1.1	16
136	Harmonic content and time variation of electron energy distributions in high-plasma-density, low-pressure inductively coupled discharges. Journal of Applied Physics, 2003, 94, 2223-2233.	1.1	5
137	Self-consistent three-dimensional model of dust particle transport and formation of Coulomb crystals in plasma processing reactors. Journal of Applied Physics, 2002, 92, 6451-6460.	1.1	36
138	Two-dimensional modeling of long-term transients in inductively coupled plasmas using moderate computational parallelism. II. Ar/Cl2 pulsed plasmas. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2002, 20, 325-334.	0.9	45
139	Two-dimensional modeling of long-term transients in inductively coupled plasmas using moderate computational parallelism. I. Ar pulsed plasmas. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2002, 20, 313-324.	0.9	41
140	Monte Carlo Simulation of the Electrodeposition of Copper. Journal of the Electrochemical Society, 2002, 149, C396.	1.3	34
141	Electron energy distributions and anomalous skin depth effects in high-plasma-density inductively coupled discharges. Physical Review E, 2002, 66, 066411.	0.8	52
142	Inflight electron impact excitation in ionized metal physical vapor deposition. Journal of Applied Physics, 2001, 89, 878-882.	1.1	10
143	Investigations of surface reactions during C2F6 plasma etching of SiO2 with equipment and feature scale models. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2001, 19, 524-538.	0.9	147
144	Trench filling by ionized metal physical vapor deposition. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2001, 19, 2652-2663.	0.9	59

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145	Noncollisional heating and electron energy distributions in magnetically enhanced inductively coupled and helicon plasma sources. Journal of Applied Physics, 2001, 90, 3699-3712.	1.1	38
146	Pulsed inductively coupled chlorine plasmas in the presence of a substrate bias. Applied Physics Letters, 2001, 79, 2145-2147.	1.5	24
147	Wave propagation and power deposition in magnetically enhanced inductively coupled and helicon plasma sources. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2001, 19, 76-86.	0.9	53
148	Mechanisms for CF2 radical generation and loss on surfaces in fluorocarbon plasmas. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2000, 18, 2661-2668.	0.9	62
149	A Monte-Carlo model of xenon resonance radiation transport in a plasma display panel cell: Transition from optically thick to thin regimes. Journal of Applied Physics, 2000, 87, 2700-2707.	1.1	15
150	Plasma abatement of perfluorocompounds in inductively coupled plasma reactors. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2000, 18, 213-231.	0.9	65
151	Interaction between soot particles and NOx during dielectric barrier discharge plasma remediation of simulated diesel exhaust. Journal of Applied Physics, 2000, 88, 6060-6071.	1.1	63
152	Consequences of propene and propane on plasma remediation of NOx. Journal of Applied Physics, 2000, 88, 3739-3747.	1.1	63
153	Controller design issues in the feedback control of radio frequency plasma processing reactors. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 1999, 17, 704-712.	0.9	14
154	Dynamics of a coplanar-electrode plasma display panel. II. Cell optimization. Journal of Applied Physics, 1999, 85, 3470-3476.	1.1	65
155	Design issues in ionized metal physical vapor deposition of copper. Journal of Applied Physics, 1998, 83, 35-43.	1.1	59
156	The effect of radio frequency plasma processing reactor circuitry on plasma characteristics. Journal of Applied Physics, 1998, 83, 5087-5094.	1.1	69
157	Diagnostic technique for measuring plasma parameters near surfaces in radio frequency discharges. Applied Physics Letters, 1998, 73, 2730-2732.	1.5	9
158	Comparison of two-dimensional and three-dimensional models for profile simulation of poly-Si etching of finite length trenches. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 1998, 16, 3274-3280.	0.9	20
159	Consequences of three-dimensional physical and electromagnetic structures on dust particle trapping in high plasma density material processing discharges. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 1998, 16, 2454-2462.	0.9	14
160	Ion composition of expanding microdischarges in dielectric barrier discharges. Journal of Applied Physics, 1998, 83, 7522-7532.	1.1	36
161	Multiple microdischarge dynamics in dielectric barrier discharges. Journal of Applied Physics, 1998, 84, 4153-4160.	1.1	51
162	Plasma transport around dust agglomerates having complex shapes. Journal of Applied Physics, 1998, 83, 5670-5677.	1.1	10

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163	Reactions in the afterglow of time modulated inductive discharges of Xe and I2 mixtures. Journal of Applied Physics, 1998, 84, 4727-4730.	1.1	4
164	Shapes of agglomerates in plasma etching reactors. Journal of Applied Physics, 1997, 81, 5960-5965.	1.1	21
165	Integrated plasma equipment model for polysilicon etch profiles in an inductively coupled plasma reactor with subwafer and superwafer topography. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 1997, 15, 1913-1921.	0.9	83
166	A semianalytic radio frequency sheath model integrated into a two-dimensional hybrid model for plasma processing reactors. Journal of Applied Physics, 1997, 81, 569-577.	1.1	72
167	Ion-ion neutralization of iodine in radio-frequency inductive discharges of Xe and I2 mixtures. Journal of Applied Physics, 1997, 82, 2150-2155.	1.1	3
168	Simulation of the formation of two-dimensional Coulomb liquids and solids in dusty plasmas. Journal of Applied Physics, 1997, 82, 2106-2114.	1.1	17
169	Consequences of asymmetric pumping in low pressure plasma processing reactors: A three-dimensional modeling study. Journal of Applied Physics, 1997, 82, 5312-5320.	1.1	36
170	Model for noncollisional heating in inductively coupled plasma processing sources. Journal of Applied Physics, 1997, 81, 5966-5974.	1.1	55
171	Argon metastable densities in radio frequency Ar, Ar/O2 and Ar/CF4 electrical discharges. Journal of Applied Physics, 1997, 82, 2805-2813.	1.1	188
172	Ion drag effects in inductively coupled plasmas for etching. Applied Physics Letters, 1996, 68, 903-905.	1.5	34
173	A threeâ€dimensional model for inductively coupled plasma etching reactors: Azimuthal symmetry, coil properties, and comparison to experiments. Journal of Applied Physics, 1996, 80, 1337-1344.	1.1	102
174	The effect of CO2 on the plasma remediation of NxOy. Applied Physics Letters, 1996, 68, 2064-2066.	1.5	15
175	Formation of XeI(B) in low pressure inductive radio frequency electric discharges sustained in mixtures of Xe and I2. Journal of Applied Physics, 1996, 80, 5593-5597.	1.1	18
176	A time dependent propagator method for long mean free path transport of neutral particles in plasma processing reactors. Journal of Applied Physics, 1996, 79, 3423-3431.	1.1	8
177	Evidence for inelastic processes for N+3and N+4from ion energy distributions in He/N2radio frequency glow discharges. Journal of Applied Physics, 1996, 79, 93-98.	1.1	7
178	Modeling of high power semiconductor switches operated in the nonlinear mode. Journal of Applied Physics, 1996, 79, 2084-2090.	1.1	21
179	Predictions of ion energy distributions and radical fluxes in radio frequency biased inductively coupled plasma etching reactors. Journal of Applied Physics, 1996, 79, 2275-2286.	1.1	86
180	Regimes of particle trapping in inductively coupled plasma processing reactors. Applied Physics Letters, 1996, 68, 3716-3718.	1.5	22

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181	Electronâ€beam controlled radio frequency discharges for plasma processing. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 1996, 14, 2094-2101.	0.9	33
182	A model for transport and agglomeration of particles in reactive ion etching plasma reactors. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 1996, 14, 562-566.	0.9	22
183	Characteristics of an optically activated pulsed power GaAs(Si:Cu) switch obtained by twoâ€dimensional modeling. Journal of Applied Physics, 1995, 77, 3518-3522.	1.1	9
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